

ABSTRACT

This invention is a cleaning method of a film-forming unit that forms a thin film on an object to be processed by supplying a process gas into a reaction chamber containing the object to be processed, the method comprising a purging step of purging an inside of the reaction chamber by supplying into the reaction chamber a nitrogen-including gas that includes nitrogen and that is capable of being activated. The purging step has a step of nitriding a surface of a member in the reaction chamber by activating the nitrogen-including gas.